

ABSTRACT OF THE DISCLOSURE

A pattern writing apparatus for writing a pattern on a photosensitive material comprises a head provided with a DMD having a micromirror group which modulates reflected light, a stage holding a substrate, and mechanisms for moving the head and the 5 stage relative to each other. In the pattern writing apparatus, for pattern writing, an irradiation region group on a substrate, which corresponds to the micromirror group of the DMD, is scanned in a main scanning direction that is angled relative to the direction of arrangement of the irradiation region group. The irradiation region group is also intermittently moved in the sub-scanning direction by a distance shorter than the width of the 10 irradiation region group in the sub-scanning direction, for pattern writing of the entire substrate. Thus, even with slight changes in an intermittent travel distance (A) of the irradiation region group, light is suitably applied to a region between strips (71, 72), whereby high-precision high-speed pattern writing is achieved.